

STD LSNitride2 5/9/2018	NEW RECIPE
Date	12/14/18
Standard LS Nitride2 Coat	
Coat time, min	10
Standard LS Nitride2 Deposition	
Depositon time, min	30
LF power setup, W	90
RF power setup, W	30
LF time, sec	2.25
HF time, sec	6
Pressure, mTorr	800
Gass flow, sccm	
2%SiH	520
NH3	18
N2	980
T, C	~300
Thickness, nm	222.28
Dep.rate, nm/min	7.41
Index at 632.8nm	1.969
Index at 1550nm	1.933
Stress, MPa	-24.86
BHF, nm/min	24.31
Std. clean, min	40